Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1492	134/94.1.CCLS. OR 134/99.1. CCLS. OR 134/100.1.CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 12:01
L3	2760	134/102.1 OR 134/902.CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 12:02
L4	2340	134/34.CCLS. OR 134/25.4.CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 12:02

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	88	((wafer or substrate or semiconductor) near10 (wash or washing or clean$8 or rins$8 or etch$8 or decontaminat$8 or flush$8) and ((foam or bubbles or froth$7 or lather or suds) near15 (water near15 ("reactive gas" or ozone or argon))))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 09:25

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S11	42	((wafer or substrate or semiconductor) near10 (wash or washing or clean$8 or rins$8 or etch$8 or decontaminat$8 or flush$8)) and (FOAM$8 NEAR15 (ARGON OR OZONE))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 09:57

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L6	336	(wafer or substrate or semiconductor) AND (FOAM$8 NEAR15 (ARGON OR OZONE))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 11:02
L10	14	("6090217" or "6296715" or "6439247") and (ozone or argon or (gas near5 reactive))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/28 11:09